

# Space-charge-limited conduction mechanism II

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# 1. Space-charge-limited flow

- One-carrier space-charge-limited flow without traps. (electrons)
- One-carrier space-charge-limited flow with traps.
- Two-carrier space-charge-limited flow without traps or recombination centers. (cathode electrons, anode holes)
- Two-carrier space-charge-limited flow with recombination centers

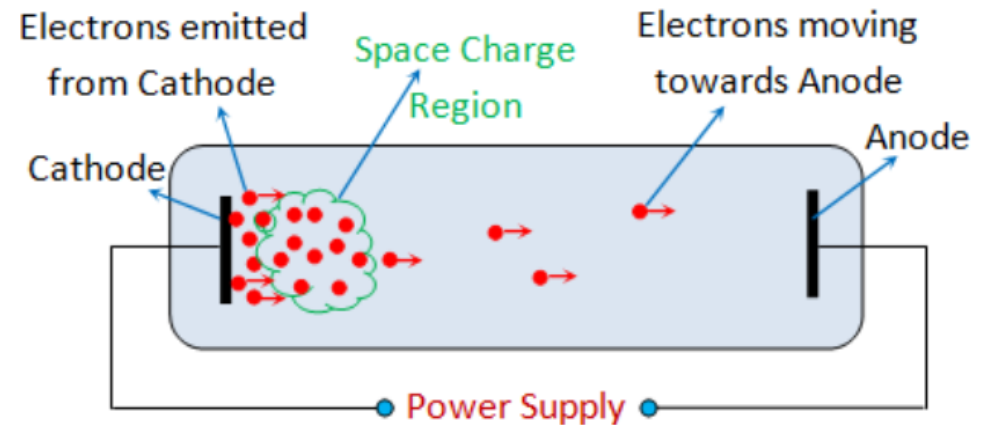
# 2. One-carrier space-charge-limited

Definition: if an electron injecting contact is applied to an insulator, electrons will travel from the metal into the conduction band of the insulator and form a **space-charge** similar to that of a **vacuum diode**.

Accumulation of charges in a particular region is referred to as **space charge**.

In vacuum (Child's law):

$$J = \frac{I_a}{S} = \frac{4\epsilon_0}{9} \sqrt{2e/m_e} \frac{V_a^{3/2}}{d^2}.$$



### 3. Theory

- At low voltages where the injected carrier density is less than  $n_0$ , which is the thermally generated free carrier density, Ohm's law will be obeyed:

$$J = en_0\mu \frac{V}{s} \quad (1)$$

- At transition voltage,  $V_{tr}$ , the transition from Ohm's law to **Mott and Gurney law** takes place:

$$J = \frac{9}{8}k\mu \frac{V^2}{s^3} \quad (2)$$

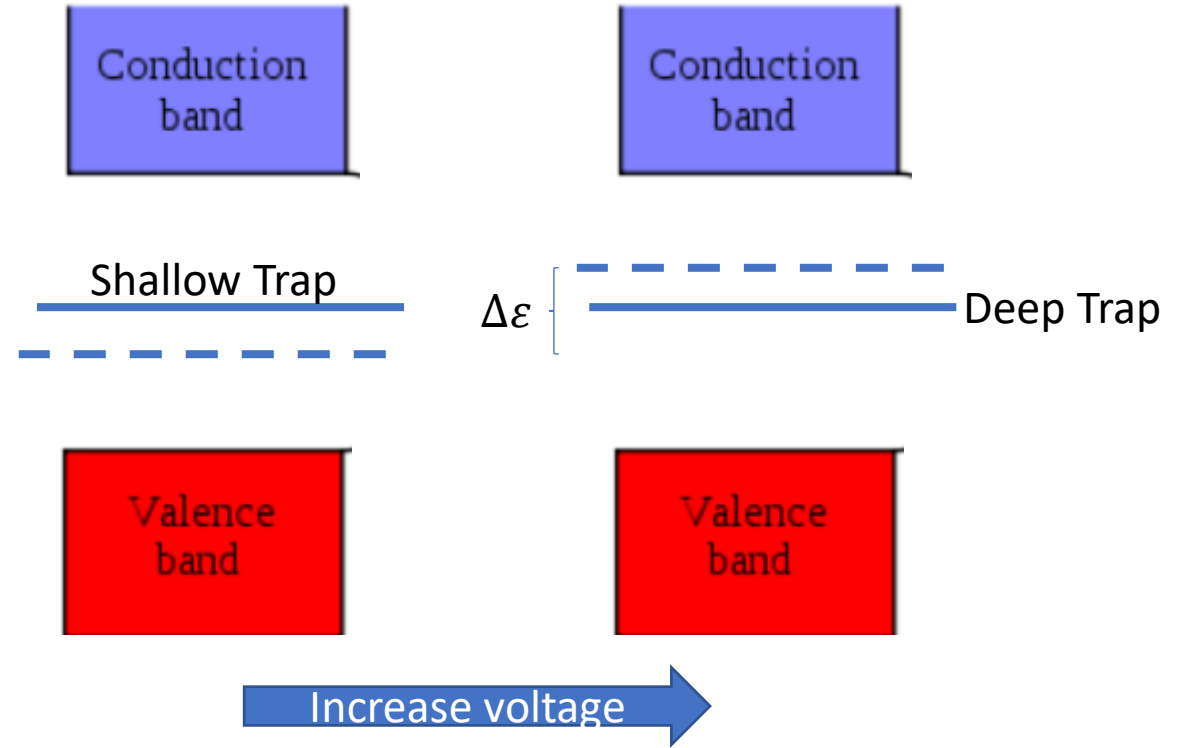
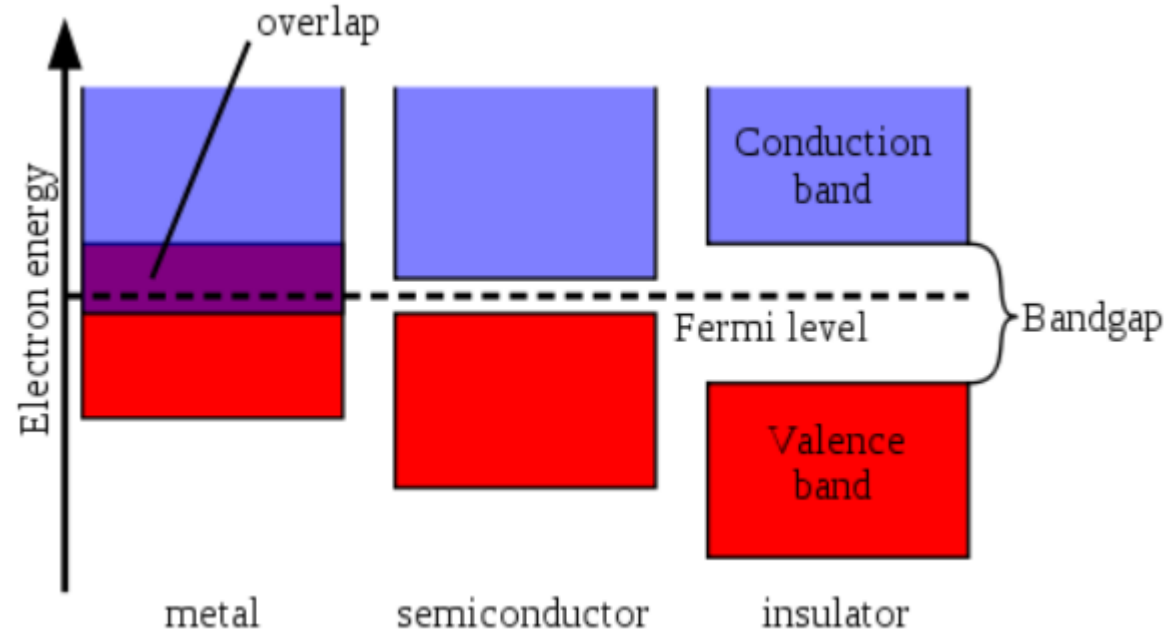
The theory is based on purely field driven currents and diffusion current:

$$J = ne\mu E - De\left(\frac{dn}{dx}\right) \quad (3)$$

s: film thickness  
 $\mu$ : mobility  
V: voltage  
k: dielectric constant  
n: free electron density  
D: diffusion coefficient



### 3. Shallow and deep trapping



Free electron density:  $n(x) = N_c \exp\left[\frac{(\epsilon_F - \epsilon_c)}{k_B T}\right]$

$N_c$ : effective density of states in the conduction band  
 $\epsilon_F$ : Fermi level  
 $\epsilon_t$ : trap level  
 $\epsilon_c$ : bottom of conduction band

### 3. Shallow and deep trapping

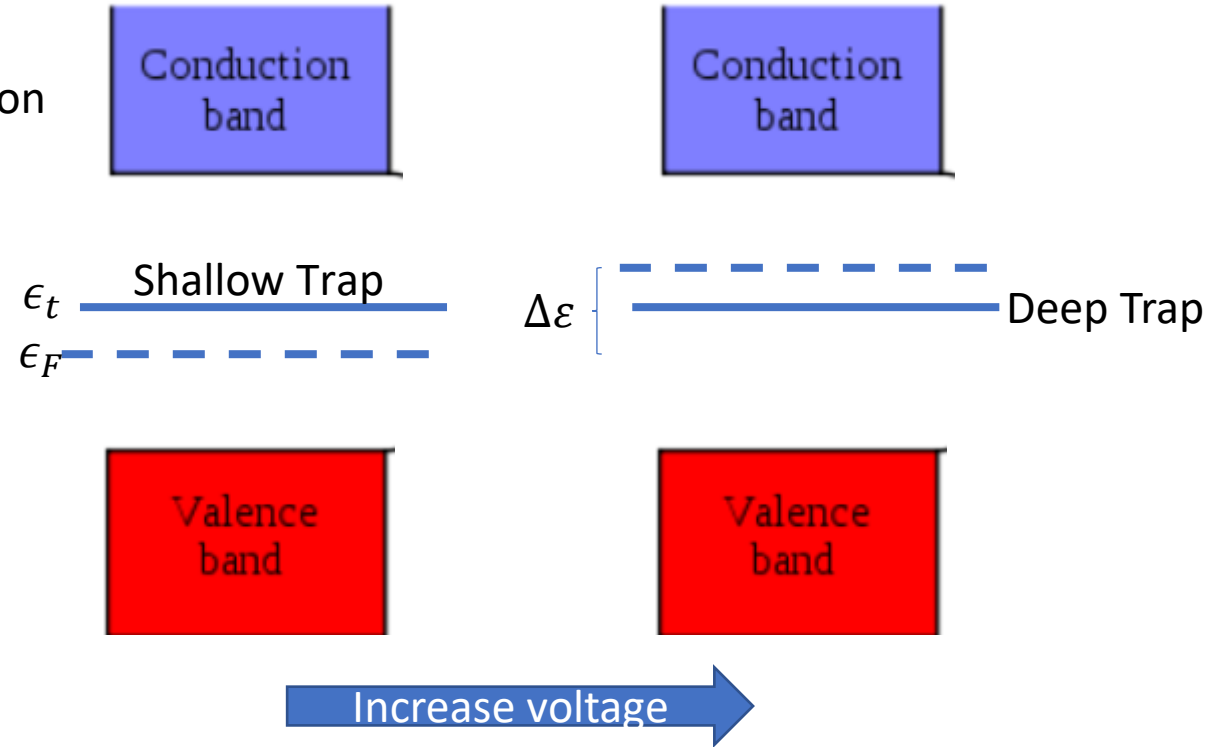
Trapped charge density (occupancy of trap):

$$n_t = \frac{N_t}{1 + \frac{1}{g} \exp[(\epsilon_t - \epsilon_F)/k_B T]}$$

Fermi-Dirac distribution

For shallow trap:  $n_t \approx \frac{N_t}{\frac{1}{g} \exp[(\epsilon_t - \epsilon_F)/k_B T]}$

For deep trap:  $n_t = N_t$



$N_t$ : trap density  
 $\epsilon_F$ : Fermi level  
 $\epsilon_t$ : trap level  
 $\epsilon_c$ : bottom of conduction band

### 3. Shallow and deep trapping

Thus the ratio of free to trapped charge is

$$\theta = \frac{n(x)}{n_t} = \frac{N_c \exp\left[\frac{(\epsilon_F - \epsilon_c)}{k_B T}\right]}{1 + \frac{1}{g} \exp\left[\frac{(\epsilon_t - \epsilon_F)}{k_B T}\right]}$$

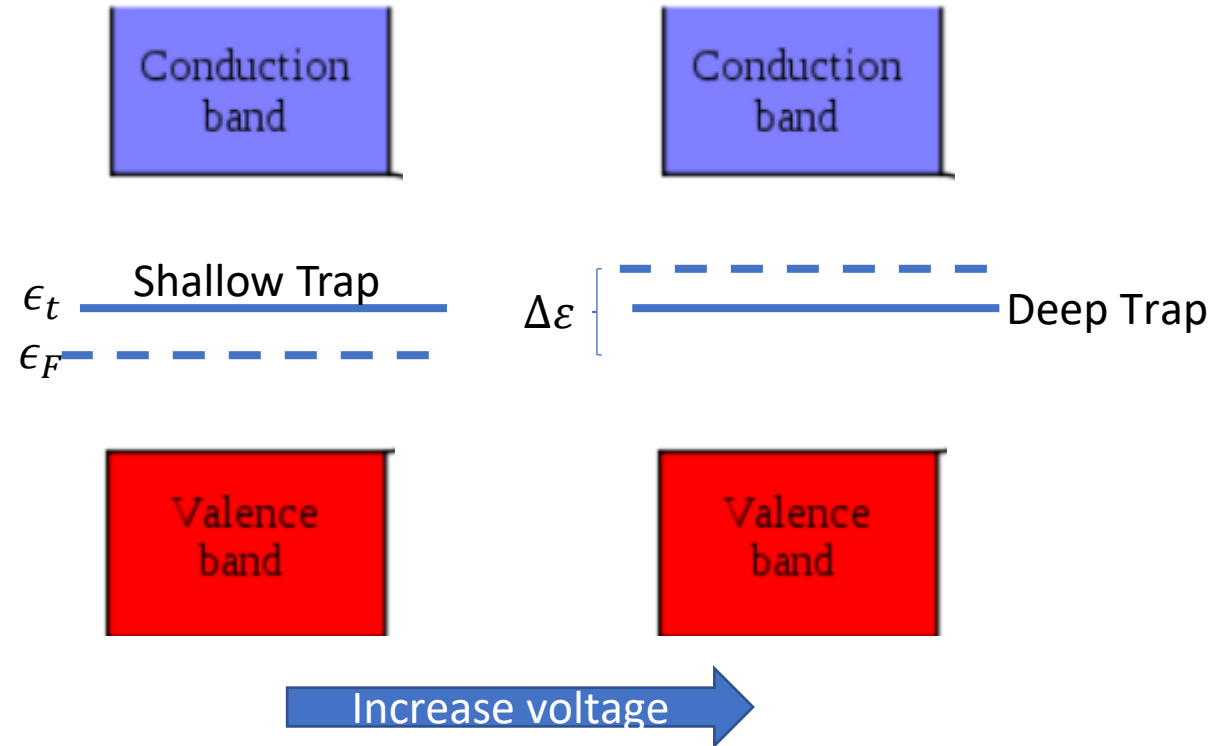
$\theta$  can be as low as  $10^{-7}$ , very large effect.

For shallow trap:  $\theta \approx \frac{N_c \exp\left[\frac{(\epsilon_t - \epsilon_c)}{k_B T}\right]}{g N_t}$

For deep trap:  $\theta = N_c \exp\left[\frac{(\epsilon_F - \epsilon_c)}{k_B T}\right] / N_t$

Therefore,

$$J = \frac{9}{8} k \mu \frac{V^2}{s^3} \quad \longrightarrow \quad J = \frac{9}{8} k \mu \theta \frac{V^2}{s^3}$$



### 3. Shallow trapping

The charge which has been injected into the insulator can be distributed in three parts:

- (1) Free charge in the conduction band
- (2) Trapped charge above the Fermi level
- (3) Trapped charge in the states between the initial Fermi level and the final Fermi level.**

Assumption that all injected charge will in fact be trapped in (3).

$$\Delta\varepsilon = \frac{Q}{eN_t s} \approx VC / (eN_t s)$$

$$n_t = \frac{Q}{es} = \frac{VC}{es}$$

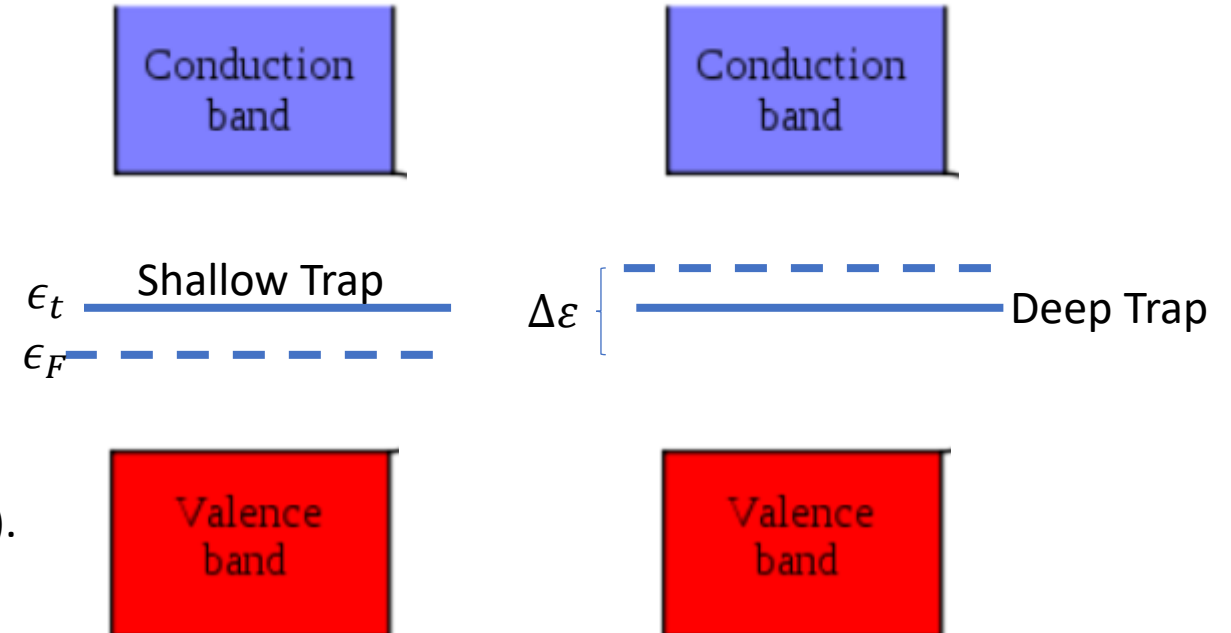
The free carrier density is given by

$$n = N_c \exp\left[\frac{(\epsilon_F - \epsilon_c)}{k_B T}\right] \exp\left[\frac{\Delta\varepsilon}{k_B T}\right]$$

$$= n_0 \exp\left[\frac{\Delta\varepsilon}{k_B T}\right] = n_0 \exp\left[\frac{VC}{eN_t s k_B T}\right] = n_0 e^{tV}$$

Hence

$$\theta = \frac{n}{n_t} = \frac{n_0 e^{tV}}{VC/es} = \frac{n_0 es}{VC} e^{tV}$$



Q: injected charge  
 $\epsilon_F$ : Fermi level  
 $\epsilon_t$ : trap level  
 $\epsilon_c$ : bottom of conduction band

Therefore,  $J = \frac{9}{8} k\mu\theta \frac{V^2}{s^3} = \frac{9}{8} k\mu \frac{V}{s^3} \left(\frac{n_0 e}{c}\right) e^{tV}$

## 4. Experiments

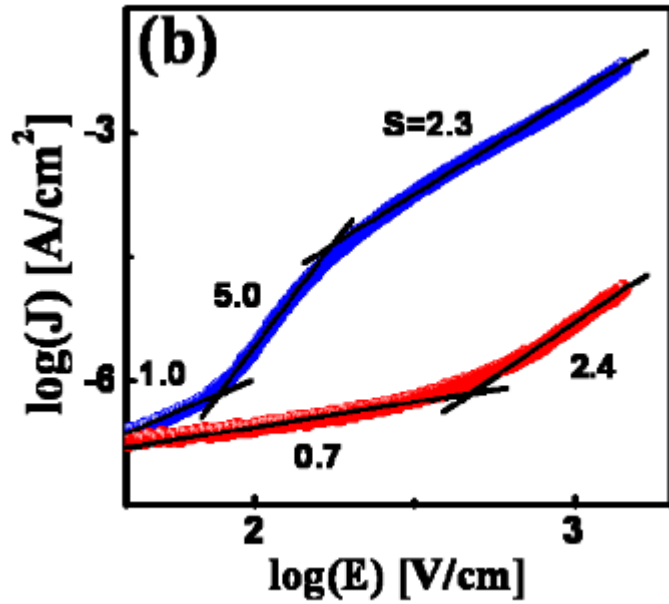
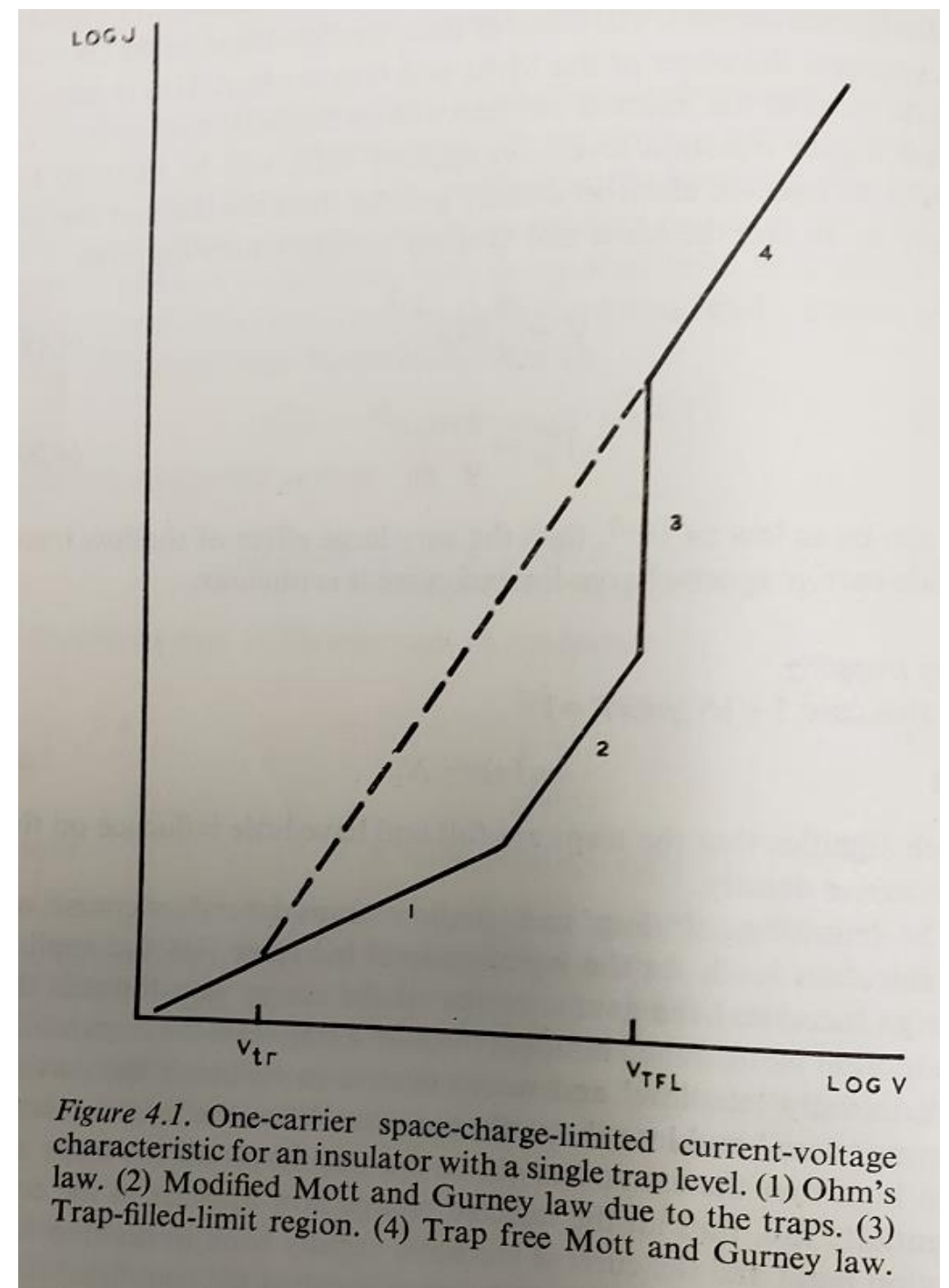


Fig. S2 Typical J-E characteristics of a Au/BFO/Au structure (BFO1) at 300 K, (b) SCLC.





## 4. Experiments

Amorphous selenium (20 u)/ tin oxide / glass substrate

For film 2, the dependence of current on voltage was between  $V$  and  $V^2$  at lower voltages.

$$I = 2.2 \times 10^{-11} V e^{V/31.1}$$

$$I = 1.3 \times 10^{-11} V e^{V/57.0}$$

For voltages less than 10 v the current was probably a mixture of ohmic and SCLC. This suggests that the thermal equilibrium Fermi level was less than  $kT$  above a uniform distribution of hole capture levels

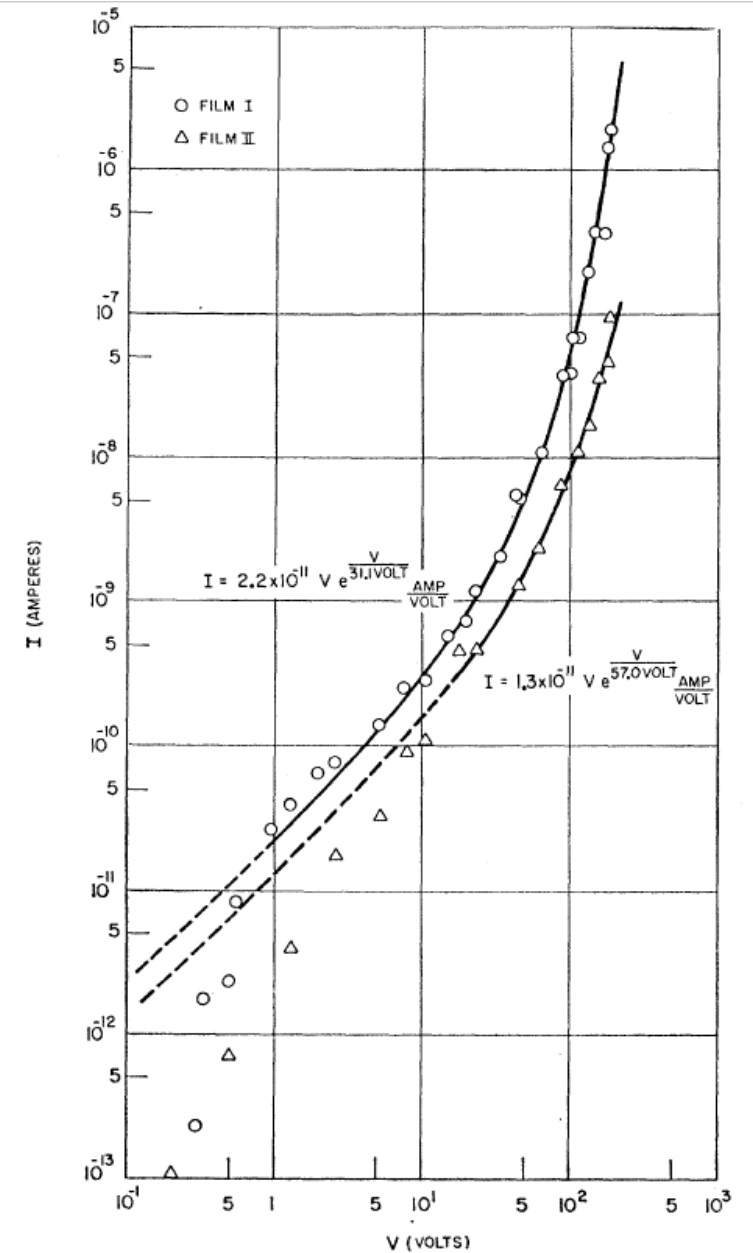


FIG. 11. Space-charge-limited currents in amorphous selenium films having gold hole-injecting contacts.

Thanks and questions?

## Derivation of Mott and Gurney law

The theory is based on purely field driven currents and diffusion current:

$$J = n\mu E - D \left( \frac{dn}{dx} \right) \quad (3)$$

Using Gauss's law and

$$\frac{n}{k} = \frac{dE}{dx}$$
$$J = k\mu E \left( \frac{dE}{dx} \right) - kD \left( \frac{d^2E}{dx^2} \right)$$

Using Einsteins' relation

$$D = \frac{\mu}{e} k_B T$$
$$J = k\mu E \left( \frac{dE}{dx} \right) - k\mu k_B T \left( \frac{d^2E}{dx^2} \right)$$

Taking  $\frac{dE}{dx} \approx \frac{E}{s}$ , if  $k_B T \ll eEs$ , one can neglect the diffusion term

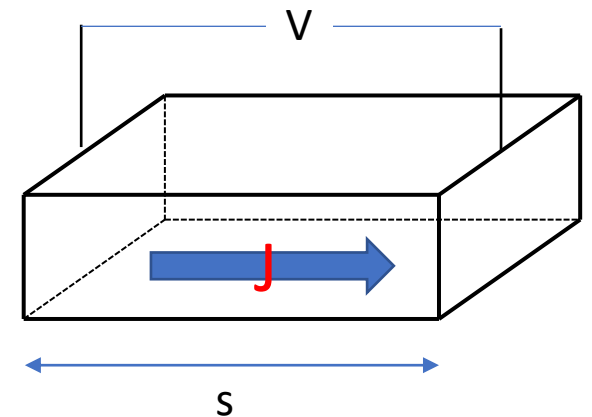
$$J = k\mu E \left( \frac{dE}{dx} \right)$$

And integrating

$$E = \sqrt{\frac{2J}{k\mu}} (x + x_0)$$

where  $x_0$  is a constant

$\mu$ : mobility  
 $n$ : charge carrier density  
 $D$ : diffusion coefficient  
 $k$ : dielectric constant



## Derivation of Mott and Gurney law

$$V = \int_0^s E dx = \int_0^s \sqrt{\frac{2J}{k\mu}} (x + x_0) dx$$
$$= \frac{2}{3} \sqrt{\frac{2J}{k\mu}} \left[ (s + x_0)^{3/2} - x_0^{3/2} \right]$$

Thus, for  $x_0 \ll s$ , neglecting  $x_0$

$$J = \frac{9}{8} k\mu \frac{V^2}{s^3}$$

The theory in fact cannot give an accurate description of the physical situation near the injecting cathode where the field will be zero and the current must be a pure diffusion current.

$\mu$ : mobility  
 $n$ : charge carrier density  
 $D$ : diffusion coefficient  
 $k$ : dielectric constant

